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(71) Applicant: **APPLIED MATERIALS, INC.** [US/US];
3050 Bowers Avenue, Santa Clara, CA 95045 (US).

(72) Inventors: **LI, Jiping**; 3510 Middlefield Road, Palo Alto, CA 94306 (US). **ADAMS, Bruce, E.**; 3411 SW 13th Street, Portland, OR 97239 (US). **THOMAS, Timothy, N.**; 11555 NW Vallevue Court, Portland, OR 97229 (US). **HUNTER, Aaron, Muir**; 430 Emeline Avenue, Santa Cruz, CA 95060 (US). **MAYUR, Abhilash, J.**; 17651 Olson Place, Salinas, CA 93907 (US). **RAMANUJAM, Rajesh, S.**; 1538 Four Oaks Circle, San Jose, CA 95131 (US).

(74) Agent: **WALLACE, Robert**; Law Office of Robert M. Wallace, 2112 Eastman Avenue, Suite 102, Ventura, CA 93003 (US).

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Declaration under Rule 4.17:

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[Continued on next page]

(54) Title: PYROMETER FOR LASER ANNEALING SYSTEM COMPATIBLE WITH AMORPHOUS CARBON OPTICAL ABSORBER LAYER

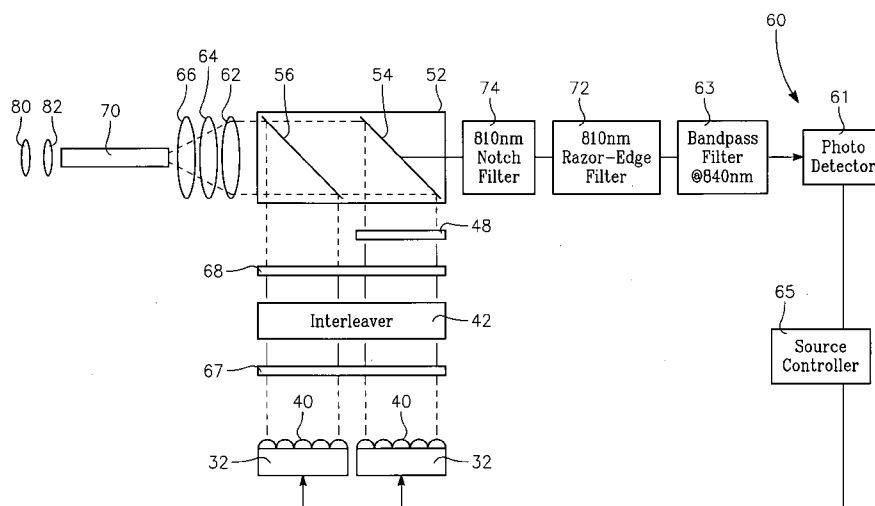


FIG. 5

(57) Abstract: In a laser annealing system for workpieces such as semiconductor wafers, a pyrometer wavelength response band is established within a narrow window lying between the laser emission band and a fluorescence emission band from the optical components of the laser system, the pyrometer response band lying in a wavelength region at which the optical absorber layer on the workpiece has an optical absorption coefficient as great as or greater than the underlying workpiece. A multi-layer razor-edge interference filter having a 5-8 nm wavelength cut-off edge transition provides the cut-off of the laser emission at the bottom end of the pyrometer response band.

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